/QE	C813	
(O, 14)	1,100	MAR
J. F	ATEM OF	

Application Number

HIS FORM IS BASED ON PTO/SB/30 (08-00)

09/891,905

## REQUEST FOR

## CONTINUED EXAMINATION (RCE) TRANSMITTAL

Subsection (b) of 35 U.S.C. § 132, effective on May 29, 2000, provides for continued examination of an utility or plant application filed on or after June 8, 1995.

See The American Inventors Protection Act of 1999 (AIPA).

Filing Date	06/26/2007	
First Named Inventor	Gwan-hyeob Koh	
Group Art Unit	2811	
Examiner Name	S. Gebremariam	
Attomey Docket Number	5649-\$73	

This is a Request for Continued Examination (RCE) under 37 C.F.R. § 1.114 of the above-identified application.

NOTE: 37 C.F.R. § 1.114 is effective on May 29, 2000. If the above-identified application was filed prior to May 29, 2000, applicant may wish to consider filing a continued prosecution application (CPA) under 37 C.F.R. § 13.53(d) (PTO/SB/29) instead of an RCE to be eligible for the patent term adjustment provisions of the AIPA. See Changes to Application Examination and Provisional Application Practice, Final Rule, 65 Fed. Reg. 50092 (Aug. 16, 2000); Interim Rule, 65 Fed. Reg. 14865 (Mar. 20, 2000), 1233 Off. Gaz. Pat. Office 47 (Apr. 11, 2000), which was established RCE practice.

Fed. Reg. 50092 (Aug. 16, 2000); Interim Rule, 65 Fed. Reg. 14865 (Mar. 20, 2000), 1233 Off. Gaz. Pat. Office 47 (Apr. 11, 2000), which was established RCE practice.		
1. Submission required under 37 C.F.R. § 1.114  a. Previously submitted i. Consider the amendment(s)/reply under 37 C.F.R. § 1.116 previously filed on		
i. Amendment Accompanying RCE 01 FC::1801 750.00 CH ii. Affidavit(s)/Declaration(s) iii. Information Disclosure Statement (IDS) iv. Other		
2. Miscellaneous		
a. Suspension of action on the above-identified application is requested under 37 C.F.R. § 1.103(c) for a period of months. (Period of suspension shall not exceed 3 months; Fee under 37 C.F.R. § 1.17(i) required)  b. Other		
3. Fees The RCE fee under 37 C.F.R. § 1.17(e) is required by 37 C.F.R. § 1.114 when the RCE is filed.		
a.  The Director is hereby authorized to charge the following fees, or credit any overpayments, to Deposit Account No. 50-0220.  i.  RCE fee (\$750) required under 37 C.F.R. § 1.17(e)  ii.  Extension of time fee (37 C.F.R. § § 1.136 and 1.17)  iii.  Other  b.  Check in the amount of \$		
SIGNATURE OF APPLICANT, ATTORNEY, OR AGENT REQUIRED		
Name (Print/Type) Robert N. Crouse Registration No. (Attorney/Agent) 44,635		
Signature Date January 23, 2003		
CERTIFICATE OF MAILING OR TRANSMISSION  I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, Box RCE, Washington, DC 20231, or facsimile transmitted to the U.S. Patent and Trademark Office on:		
Name (Print/Type) Susan E. Freedman		
Signature Susan E. Muduan Date January 23, 2003		



Attorney Docket No.: 5649-873

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re: Koh et al.

Serial No.: 09/891,905

Filed: June 26, 2001

Group Art Unit: 2811

Examiner: Samuel A. Gebremariam

Confirmation No.:1424

r: METHODS OF FORMING INTEGRATED CIRCUITS USING MASKS TO

PROVIDE ION IMPLANTATION SHIELDING TO PORTIONS OF SUBSTRATE ADJACENT TO AN ISOLATION REGION THEREIN

January 23, 2003

BOX RCE Commissioner for Patents Washington, DC 20231

## AMENDMENT ACCOMPANYING RCE

Sir:

This Amendment is responsive to the Final Official Action of October 23, 2002 and the Advisory Action of January 3, 2003. Pursuant to the rules for amendments under 37 C.F.R. § 1.121, the claims have been amended herein using the rewritten claims format. The present amendment also includes a section entitled "VERSION WITH MARKINGS TO SHOW CHANGES MADE" attached hereto.

## In the Claims:

Please replace Claims 1 and 21 with the following like numbered claims:

Sub 1

D) \ \ \ (Twice Amended) A method of forming a channel region between isolation regions of an integrated circuit substrate, the method comprising:

forming a mask on the isolation region that extends onto a portion of the substrate adjacent to the isolation region to provide a shielded portion of the substrate adjacent to the isolation region and an exposed portion of the substrate spaced apart from the isolation region having the shielded portion therebetween, the exposed portion of the substrate comprising a first portion where a gate electrode will be subsequently formed and a second portion where a bit line contact will be subsequently formed, the mask exposing only the first and second portions;